

REMARKS1. Amendments to the Specification

To facilitate claiming priority, Applicants have amended the written specification. Specifically, the present application is a divisional of U.S. Patent Application No. 09/976,681 filed on October 12, 2001 entitled "Template Design for Room Temperature, Low Pressure Micro- and Nanoimprint Lithography," which claims priority to U.S. Provisional Patent Application No. 60/239,808 filed on October 12, 2000 entitled "Template Design for Room Temperature, Low Pressure Micro- and Nanoimprint Lithography and Method for Sensing Gap or Film Thickness," and is a divisional of U.S. Patent Application No. 09/907,512 filed on July 16, 2001 entitled "High-Resolution Overlay Alignment Methods and Systems for Imprint Lithography," which claims priority to U.S. Provisional Patent Application No. 60/218,568 filed on July 16, 2000 entitled "High-Resolution Overlay Alignment Methods and Systems for Imprint Lithography," all of which are incorporated by reference herein. No new matter has been introduced by the amendments.

Applicant respectfully requests examination in view of the remarks. A notice of allowance is earnestly solicited.

CERTIFICATE OF MAILING

I hereby certify that this paper (along with any paper referred to as being attached or enclosed) is being deposited with the United States Postal Service on the date shown below with sufficient postage as first class mail in an envelope addressed to: Mail Stop PATENT APPLICATION, Alexandria, VA 22313

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March 11, 2004

Respectfully Submitted,



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